

# A Salute to the MRS Headquarters Staff

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MRS

It is a well-known fact that the success of an organization hinges on the productivity of individuals. Individuals who are highly motivated, who like their jobs, and who gain personal satisfaction from their contributions are an organization's greatest assets.

MRS is the product of two types of individuals—the member volunteer and the staff member. It is relatively obvious why volunteers work for the Society. However, while current statistics indicate that about 80% of U.S. workers do not like their jobs, it is equally obvious that the MRS Headquarters staff are not among them. Instead, they belong to that special 20% whose enthusiasm, hard work, professionalism, and responsiveness provided a key factor in the many achievements MRS enjoyed this year.

The staff often work long hours, especially before abstract and publishing deadlines and in preparation of MRS meetings. They understand, among other things, how to work with the volunteers, who have very tight schedules. It has certainly been a pleasure for me, the officers, and any other MRS volunteers to work closely with them and to share in the many achievements of the Society over the past 12 months.

Several changes made this year will help the Headquarters staff to continue contributing to the Society in very special ways in the coming year. During the summer, the Headquarters moved to a larger office space where a better working environment will enable the staff to accommodate our ever-expanding activities and implement new projects. Currently in progress is the installation of a new computer which will accelerate both the flow of information and response time in handling meeting abstracts and other Society interactions. A new retirement plan was also implemented as a staff benefit this year.

The role filled by the dedicated individuals on the MRS staff has been fundamental in making this year's MRS activities successful. On behalf of MRS, I wish to thank Executive Director John Ballance and the entire Headquarters staff for their contributions to our Society in 1989.

R.P.H. Chang



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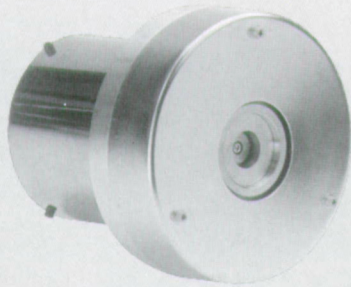
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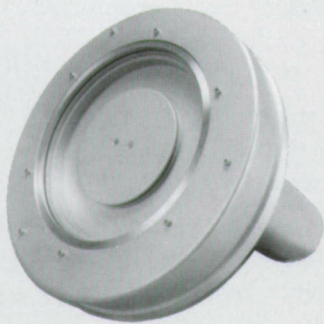
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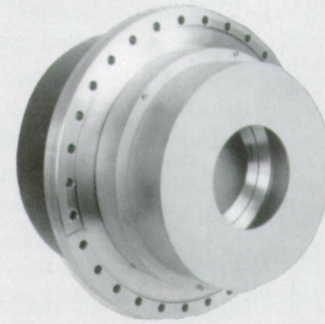
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† VLSI Research, Inc. 1988

‡ See technical papers by Cumo of IBM and Clarke of SFI for discussion of negative ion effect during reactive sputtering of oxides.

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